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(12) **United States Design Patent** (10) **Patent No.:** **US D956,361 S**
Zhu (45) **Date of Patent:** **** Jun. 28, 2022**

(54) **FACE MASK**
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(**) Term: **15 Years**
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(52) **U.S. Cl.**
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(58) **Field of Classification Search**
USPC D2/866; D24/110.1, 110.2, 127;
D29/105, 107, 108, 110, 129
CPC A41D 13/11; A41D 13/1107; A41D
13/1161; A42B 3/225
See application file for complete search history.

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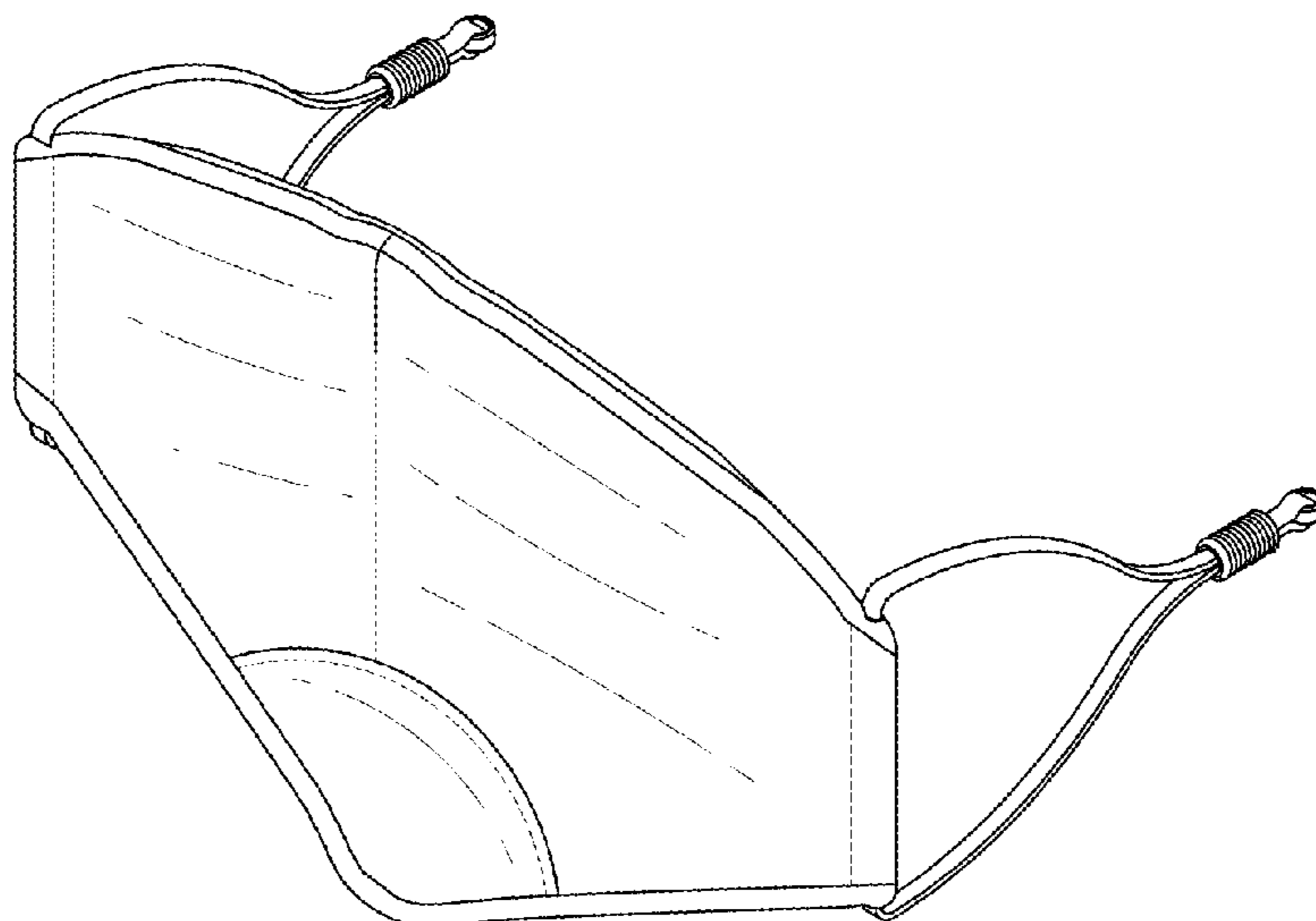
(57) **CLAIM**

What is claimed is an ornamental design for a face mask, as shown.

DESCRIPTION

FIG. 1 is a perspective view of a face mask showing our new design;
FIG. 2 is a frontal elevational view thereof;
FIG. 3 is a rear elevational view thereof;
FIG. 4 is a top view thereof;
FIG. 5 is a bottom view thereof; and,
FIG. 6 is a side elevational view thereof.
The broken lines in the figures illustrate portion of the face mask that form no part of the claimed design.

1 Claim, 6 Drawing Sheets



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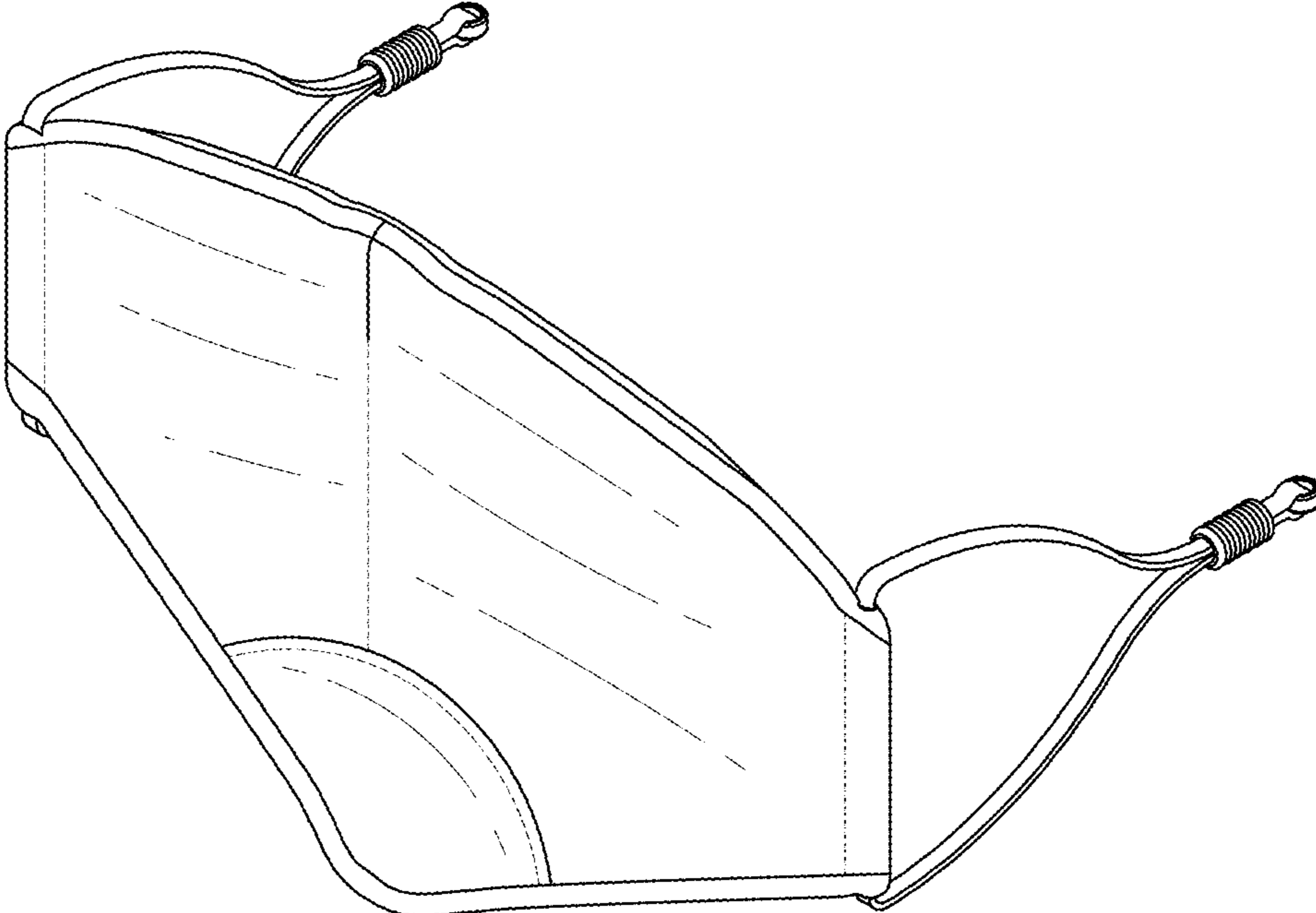


FIG. 1

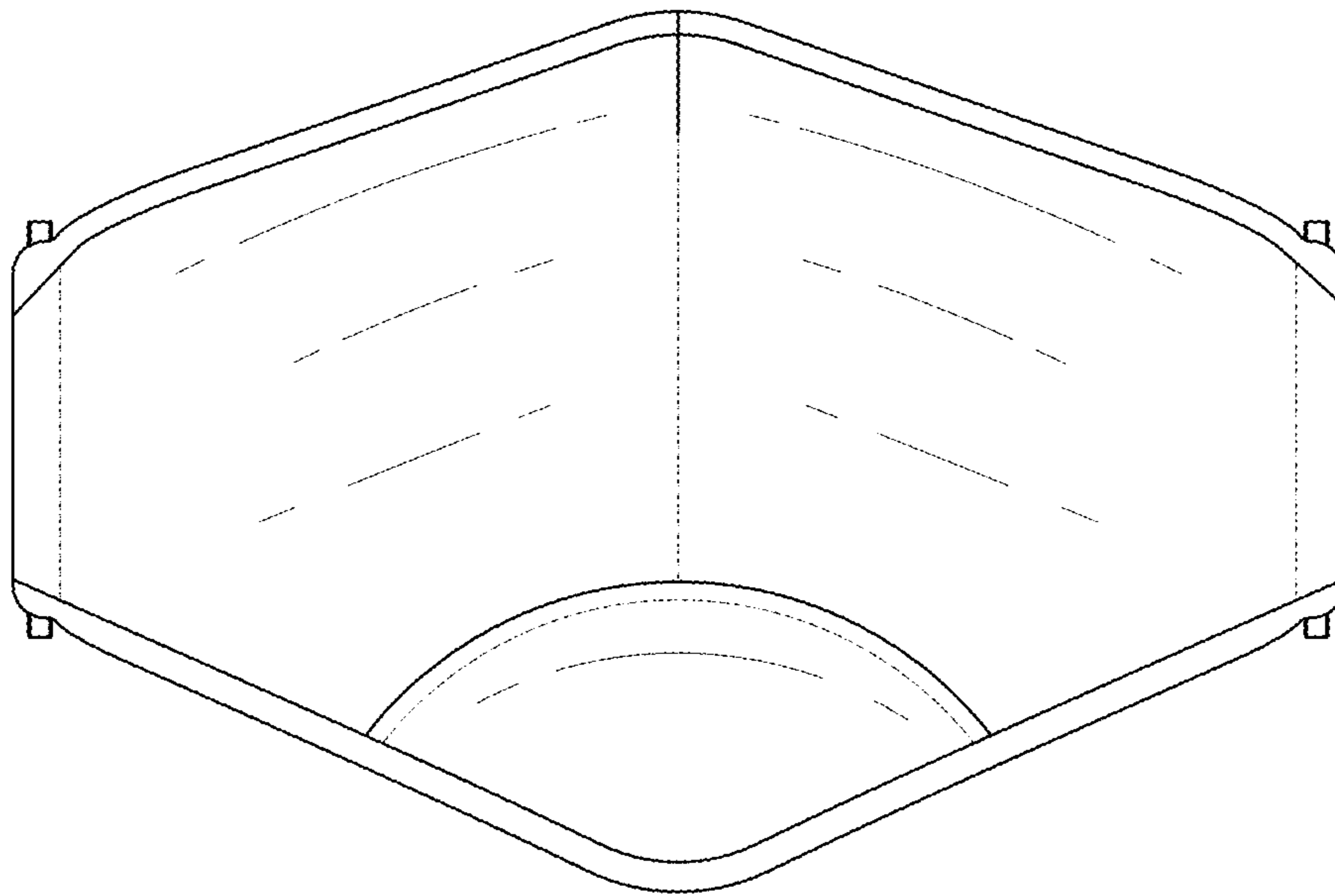


FIG. 2

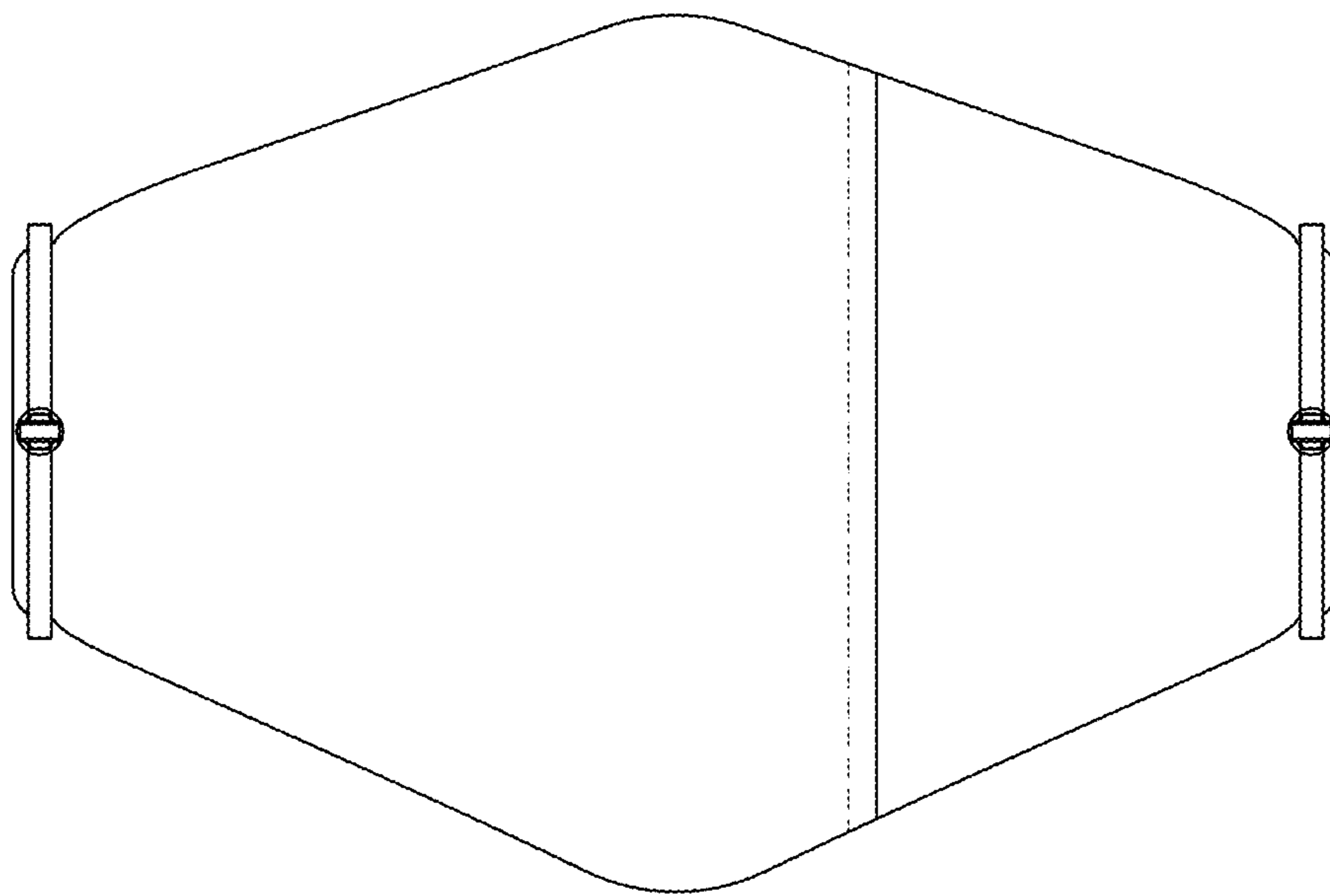


FIG. 3

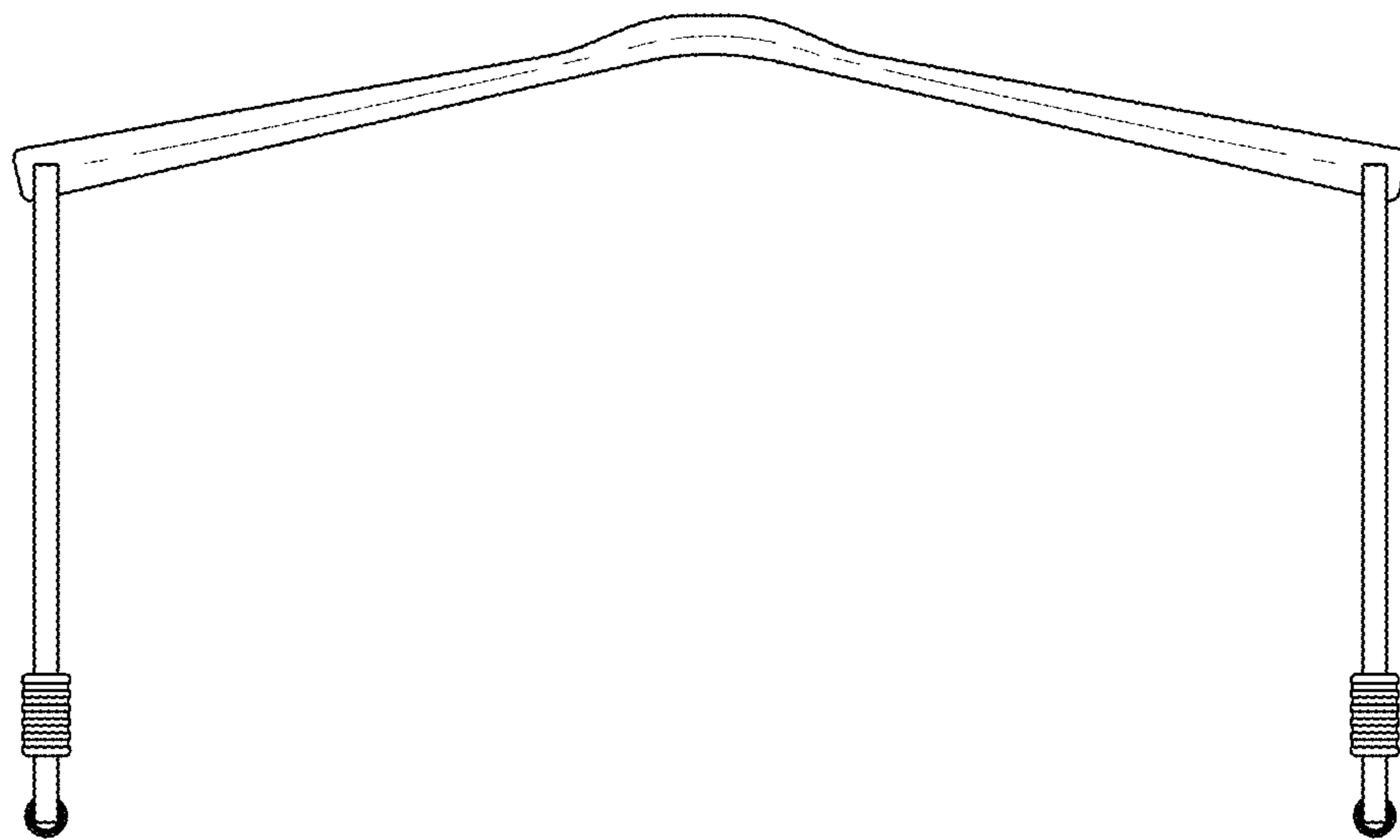


FIG. 4

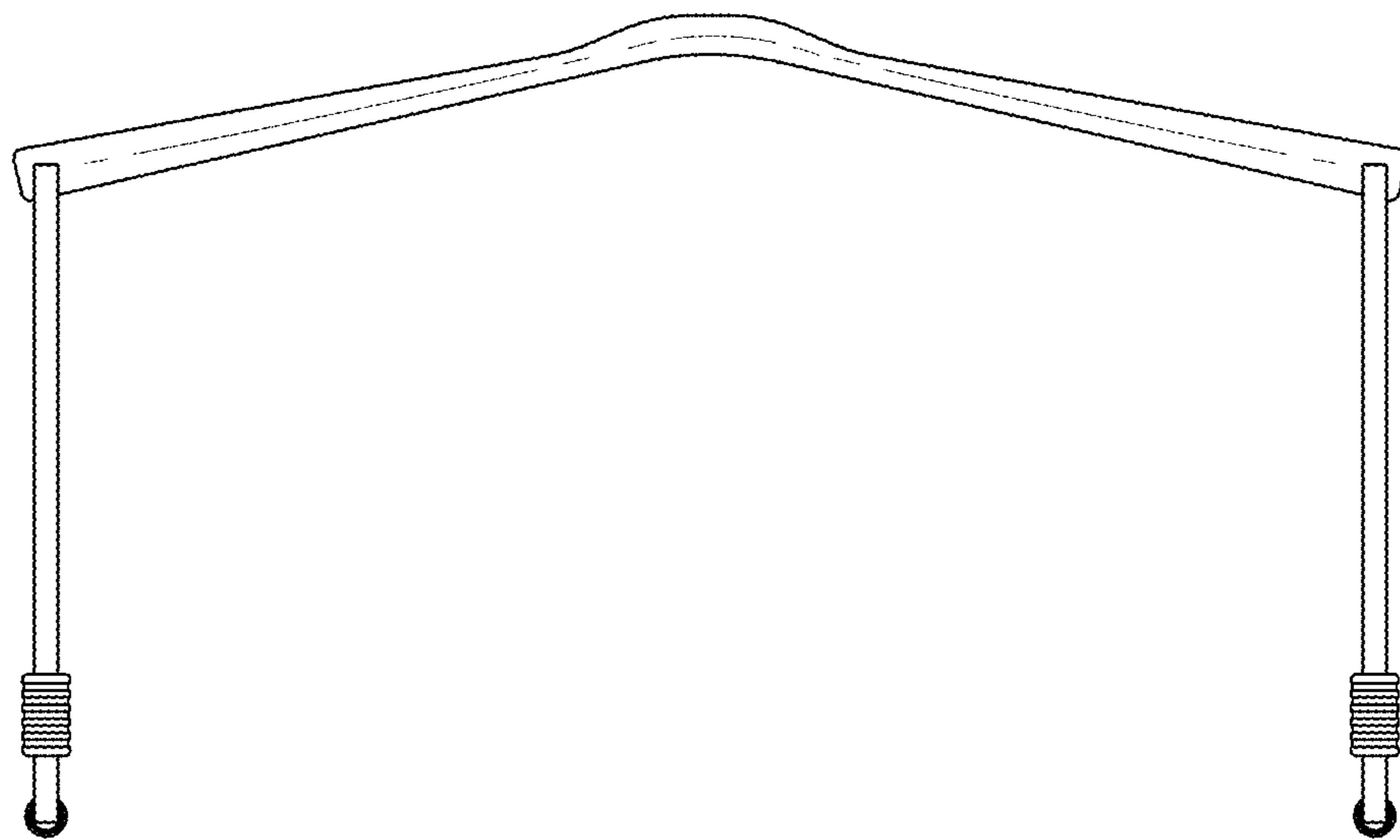


FIG. 5

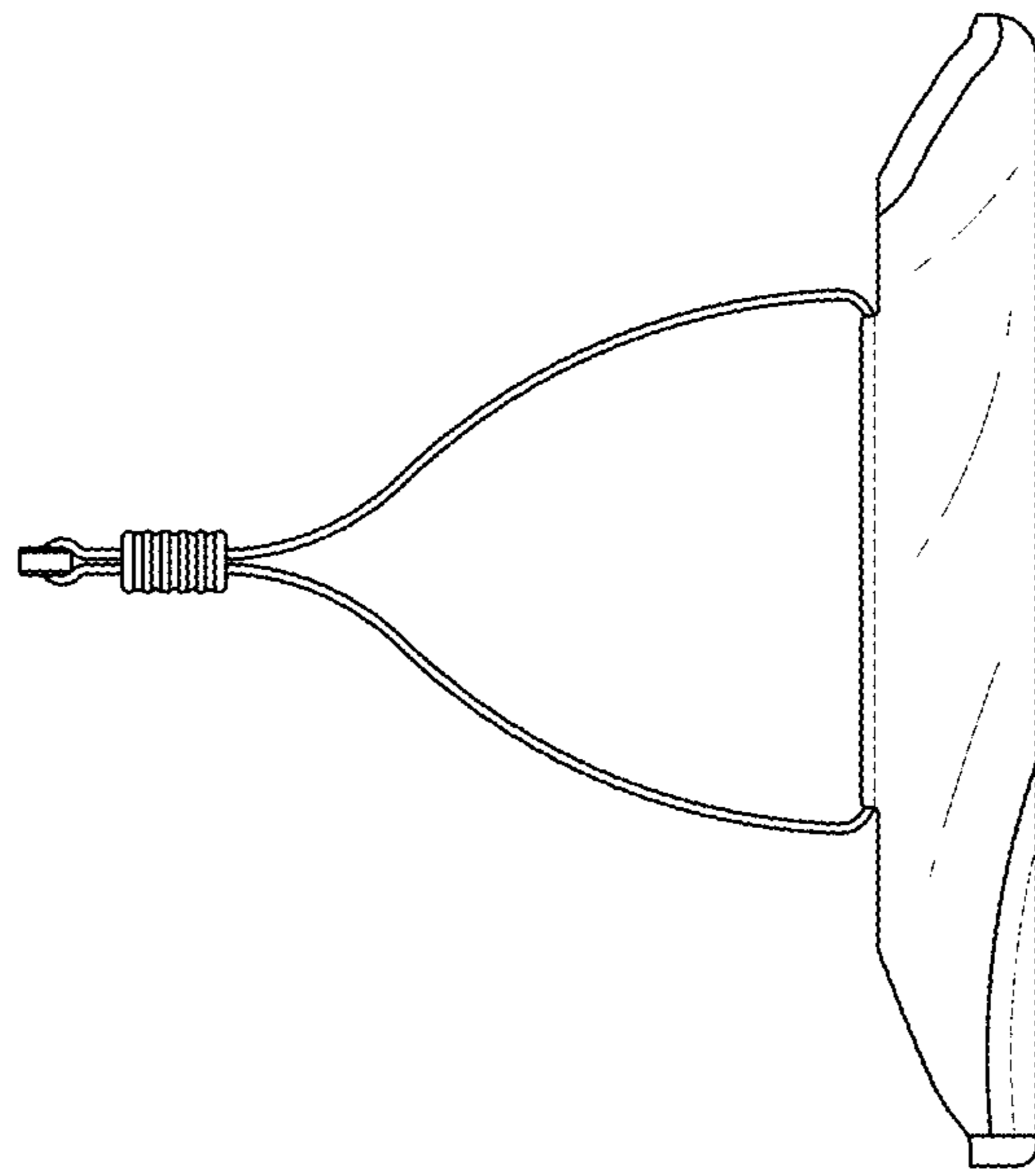


FIG. 6